

EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	8807	430/311-313,394.ccls.	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 14:33
L2	435	1 and (interlac\$3 or intertwi \$3 or double expos\$3)	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 14:35
L3	4791	1 and @ad<="20010510"	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 14:51
L4	162	2 and 3	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 14:51
L5	284	1 and 3 and (second or another or additional or extra or overlap\$4 or separate or different) (expos \$3) same (photoresist or resist) not 4	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 14:57
L6	61	1 and 3 and (develop\$4) same (photoresist or resist) same etch\$3 same (semiconductor or wafer) and (dynamic random access memory or DRAM) not 4 not 5	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:02
L7	58	1 and 3 and (round\$3 near corner or line near3 shorten \$3) not 4 not 5 not 6	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:04
L8	32	1 and 3 and (optical proximity near2 (correct\$3 or effect) or OPC) not 4 not 5 not 6 not 7	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:06
L9	1754	430/22.ccls. not 1	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:15

L10	111	(1 or 9) and 3 and (("same" or single or singular or first or one) near2 (photoresist or resist)) same ((double or two or second or overlap\$4 or stitch\$3 or overlay\$3 or over) near2 (expos\$3)) not 4 not 5 not 6 not 7 not 8	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:16
L11	406	(1 or 9) and (("same" or single or singular or first or one) near2 (photoresist or resist)) same ((double or two or second or overlap\$4 or stitch\$3 or overlay\$3) near2 (expos\$3)) not 4 not 5 not 6 not 7 not 8 not 10	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:18
L12	33	(Hwang-Jiunn-Ren or Chen-Anseime or Huang-I-Hsiung). in. and (United Microelectronics).as. not 4 not 5 not 6 not 7 not 8 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:22
L13	47	((Hwang-Jiunn-Ren or Chen-Anseime or Huang-I-Hsiung). in. or (United Microelectronics).as.) and (photoresist or resist) same (((double or two or second or overlap\$4 or stitch\$3 or overlay\$3) near2 expos\$3) and develop\$4) not 4 not 5 not 6 not 7 not 8 not 10 not 11 not 12	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 15:31
L15	11	(1 or 9) and (("same" or single or singular or first or one) near2 (photoresist or resist)) same ((multipl\$3 or plural\$3) near2 (expos\$3)) not 4 not 5 not 6 not 7 not 8 not 10 not 11	US-PGPUB; USPAT; EPO; JPO	ADJ	ON	2008/06/30 20:42

6/30/08 8:48:39 PM

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